

	Hits	Search Text	DBs
1	10	430/394.ccls. and ((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (first same mask same second same phase same (invers\$3 or revers\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
2	40	((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4) same first same (second or double or plural\$3)) and (first same mask same second same phase same (invers\$3 or revers\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
3	0	((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (first same mask same second same phase same (invers\$3 or revers\$3)) and (projection same (light\$3 or optic\$3) same bracelet)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
4	0	((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (projection same (light\$3 or optic\$3) same	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB

		bracelet)	
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	Hits	Search Text	DBs
5	2	((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((projection or light\$3 or optic\$3 or expo\$4 or illuminat\$4) same bracelet)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
6	2	((projection or light\$3 or optic\$3 or expo\$4 or illuminat\$4) same bracelet) and ((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
7	9	((projection or light\$3 or optic\$3 or expo\$4 or illuminat\$4) same bracelet) and ((mask or reticle or phase\$3shift\$4mask) same (photoresist or resist or photosensitive) same (substrate or wafer or device))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
8	17	((projection or light\$3 or optic\$3 or expo\$4 or illuminat\$4) same bracelet) and ((phase\$4shift near5 mask) or mask or reticle) and ((substrate or wafer or device) same (resist or photoresist))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
9	24	((projection or light\$3 or optic\$3 or expo\$4 or illuminat\$4 or lens or transmitt\$4) same bracelet) and ((phase\$4shift near5 mask) or mask or reticle) and ((substrate or wafer or device) same (resist or photoresist))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
10	22	430/5.ccls. and ((first near4 (mask or reticle or phase\$3shift\$4mask)) same (second near5 (mask or reticle or phase\$3shift\$4mask)) same (photoresist or resist or photosensitive) same (substrate or wafer or device) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (first same mask same second same phase same (invers\$3 or revers\$3) same shift\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB